

AUG 20 2008

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:	Michael L. McSwiney et al.	§	Art Unit:	1792
Serial No.:	10/764,193	§	Examiner:	David P. Turocy
Filed:	January 23, 2004	§	Atty Docket:	ITL.1056US P17793
For:	Forming a Silicon Nitride Film	§	Assignee:	Intel Corporation

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

OK TO ENTER: /D.T./

08/25/2008

**REPLY TO FINAL REJECTION**

Sir:

In response to the final rejection mailed July 18, 2008, please amend the above-referenced patent application as follows:

Date of deposit: AUGUST 20, 2008  
I hereby certify that this document is being facsimile transmitted to the  
United States Patent and Trademark Office (Fax No. 571/273-8300) on the  
date indicated above.  
*Cynthia L. Hayden*  
Cynthia L. Hayden